

This article was downloaded by:

On: 29 January 2011

Access details: *Access Details: Free Access*

Publisher *Taylor & Francis*

Informa Ltd Registered in England and Wales Registered Number: 1072954 Registered office: Mortimer House, 37-41 Mortimer Street, London W1T 3JH, UK



Phosphorus, Sulfur, and Silicon and the Related Elements

Publication details, including instructions for authors and subscription information:

<http://www.informaworld.com/smpp/title~content=t713618290>

Editorial board page for “Phosphorus, Sulfur, and Silicon and the Related Elements”, Volume 92, Number 1-4

To cite this Article (1994) 'Editorial board page for “Phosphorus, Sulfur, and Silicon and the Related Elements”, Volume 92, Number 1-4', Phosphorus, Sulfur, and Silicon and the Related Elements, 92: 1, a – b

To link to this Article: DOI: 10.1080/10426509408021450

URL: <http://dx.doi.org/10.1080/10426509408021450>

PLEASE SCROLL DOWN FOR ARTICLE

Full terms and conditions of use: <http://www.informaworld.com/terms-and-conditions-of-access.pdf>

This article may be used for research, teaching and private study purposes. Any substantial or systematic reproduction, re-distribution, re-selling, loan or sub-licensing, systematic supply or distribution in any form to anyone is expressly forbidden.

The publisher does not give any warranty express or implied or make any representation that the contents will be complete or accurate or up to date. The accuracy of any instructions, formulae and drug doses should be independently verified with primary sources. The publisher shall not be liable for any loss, actions, claims, proceedings, demand or costs or damages whatsoever or howsoever caused arising directly or indirectly in connection with or arising out of the use of this material.

Phosphorus, Sulfur, and Silicon and the Related Elements

Editor in Chief: R. R. Holmes

Department of Chemistry, University of Massachusetts, Amherst, Massachusetts 01003 U.S.A.

European Editor: L. Maier

R-1059, 6.08, CIBA-GEIGY AG. CH-4002, Basel, Switzerland

Associate Editors

Editor Emeritus

W. Walter

*University of Hamburg
Institut für Organische Chemie
Martin-Luther-King-Platz 6
D-2000 Hamburg 13, Germany*

J. G. Verkade

*Department of Chemistry
Iowa State University
Ames, Iowa 50010,
U.S.A.*

L. Horner

Mainz, Germany

(For Communications and Reviews)

Editorial Board

R. P. Arshinova

*Monsanto
St. Louis, Missouri*

K. D. Berlin

*Oklahoma State
University, Stillwater*

E. Block

*State University of
New York at Albany*

H. Bock

*The University
Frankfurt, Germany*

R. Burgada

*Université P. et M. Curie
Paris, France*

R. Contreras

*Centro de
Investigación de
Estudios Avanzados
del IPN, Mexico*

J. Y. Corey

*University of Missouri,
St. Louis*

R. Corriu

*University of Science
and Technology of
Languedoc, France*

S. Cremer

*Marquette University
Milwaukee, Wisconsin*

F. A. Davis

*Drexel University
Philadelphia,
Pennsylvania*

S. A. Evans, Jr.

*University of
North Carolina at
Chapel Hill*

L. Field

*Vanderbilt University
Nashville, Tennessee*

E. Fluck

*Gmelin Institute
Frankfurt, Germany*

P. Gaspar

*Washington
University
St. Louis, Missouri*

C. D. Hall

*King's College
London, UK*

S. Husebye

*University of Bergen
Norway*

N. Inamoto

*University of Tokyo
Japan*

K. Jurkschat

*Martin-Luther
University,
Halle, Germany*

J. F. King

*University of
Western Ontario
Canada*

O. I. Kolodiaznyh

*National Academy of
Sciences of Ukraine
Kiev, Ukraine*

S. S. Krishnamurthy

*Indian Institute of
Science,
Bangalore, India*

J. P. Majoral

*Université Paul
Sabatier
Toulouse, France*

S. Masson

*Université de Caen
France*

T. A. Mastryukova

*Russian Academy of
Sciences
Moscow, Russia*

F. Mathey

*Ecole Polytechnique
Palaiseau, France*

M. Mikolajczyk

*Polish Academy of
Sciences
Lodz, Poland*

G. Modena

*The University
Padua, Italy*

J. F. Nixon

*University of Sussex
Brighton, UK*

E. E. Nifant'ev

*V. I. Lenin State
Pedag. Inst.
Moscow, Russia*

S. Oae

*Institute of Heteroatom
Chemistry
Osaka, Japan*

L. D. Quin

*University of
Massachusetts
Amherst*

H. Roesky

*The University
Gottingen, Germany*

H. Sakurai

*Tohoku University
Sendai, Japan*

H. Schmidbaur

*Technical University
Munich, Germany*

A. Schmidpeter

*The University
Munich, Germany*

M. Schmidt

*The University
Würzburg, Germany*

R. Schmutzler

*The University
Braunschweig,
Germany*

R. A. Shaw

*Birkbeck College
London, UK*

R. Steudel

*Technical University of
Berlin, Germany*

B. S. Thyagarajan

*The University of
Texas at San Antonio*

J. C. Van de Grampel

*University of
Groningen
The Netherlands*

M. Veith

*Universität des
Saarlandes, Germany*

R. West

*University of
Wisconsin, Madison*

P. Wisian-Neilson

*Southern Methodist
University
Dallas, Texas*

B. Wladislaw

*University of São
Paulo, Brazil*

R. Wolf

*Université Paul
Sabatier
Toulouse, France*

C. Yuan

*Shanghai Institute of
Organic Chemistry
PRC*

H. Zimmer

*University of
Cincinnati, Ohio*

R. A. Zingaro

*Texas A&M
University
College Station*

B. Zwanenburg

*University of
Nijmegen
The Netherlands*

Aims and Scope

Phosphorus, Sulfur, and Silicon and the Related Elements welcomes submissions involving the organic, inorganic, and biochemistry of phosphorus (including arsenic, antimony, and bismuth), sulfur (including selenium and tellurium), and silicon (including germanium and tin). In addition to research describing new chemistry of a particular element, especially welcome are presentations emphasizing relationships between elements and families of elements: for example, research comparing synthetic, mechanistic, or structural features providing new insight leading to a more rapid advance of science in these areas.

Original articles, communications, and selected reviews of broad interest will be considered for publication. Manuscripts may include illustrative material in color if this will enhance the presentation. There are no page charges and 25 free reprints will be supplied to the principal author. Regular papers may be sent to R. R. Holmes in Amherst or to L. Maier in Basel. Communications and reviews should be sent to W. Walter in Hamburg or J. G. Verkade in Ames.

Notes for contributors, including information on communications and reviews, can be found at the back of the journal.

General Information

Please see the inside back cover for information on subscription rates, photocopy license, and article reprints.

© 1994 by OPA (Overseas Publishers Association) Amsterdam B.V. Published under license by Gordon and Breach Science Publishers SA, a member of The Gordon and Breach Publishing Group. All rights reserved.

Except as permitted under national laws or under the Photocopy License described below, no part of this publication may be reproduced or transmitted in any form or by any means, electronic, mechanical, photocopying or otherwise, or stored in a retrieval system of any nature, without the advance written permission of the Publisher.

Distributed by International Publishers Distributor.

Printed in the United States of America.

JULY 1994

Continued on inside back cover

Continued from inside front cover

Ordering Information

Published monthly. Subscriptions are renewed on an annual basis. 1995 Volumes: 98–107.

Orders may be placed with your usual supplier or with International Publishers Distributor at one of the addresses shown below. Journal subscriptions are sold on a per volume basis only; single issues of the current volume are not available separately. Claims for nonreceipt of issues will be honored free of charge if made within three months of publication of the issue. Subscriptions are available for microform editions; details will be furnished upon request.

All issues are dispatched by airmail throughout the world.

Subscription Rates Base list subscription price per volume: ECU 290.00 (US \$348.00). * This price is available only to individuals whose library subscribes to the journal OR who warrant that the journal is for their own use and provide a home address for mailing. Orders must be sent directly to the Publisher and payment must be made by personal check or credit card.

Separate rates apply to academic and corporate/government institutions, and may also include photocopy license and postage and handling charges.

* ECU (European Currency Unit) is the worldwide base list currency rate; payment can be made by draft drawn on ECU currency in the amount shown or in local currency at the current conversion rate. The US Dollar rate is based on the ECU rate and applies to North American subscribers only. Subscribers from other territories should contact their agents or the Publisher. All prices are subject to change without notice.

Orders and enquiries should be placed through International Publishers Distributor at one of the addresses below:

Postfach,
4004 Basel,
Switzerland
Telephone: (41-61) 261-01-38
Fax: (41-61) 261-01-73

820 Town Center Drive
Langhorne, PA 19047 USA
Telephone: (215) 750-2642
Fax: (215) 750-6343

Kent Ridge, P.O. Box 1180
Singapore 9111
Republic of Singapore
Telephone: 741-6933
Fax: 741-6922

Yohan Western Publications Distribution Agency
3-14-9, Okubo, Shinjuku-ku
Tokyo 169, Japan
Telephone: (03) 3208-0186
Fax: (03) 3208-5308

Photocopy License This publication and each of the articles contained herein are protected by copyright. If the subscription price paid by the subscriber includes a fee for a photocopy license, then the subscriber is permitted to make multiple photocopies of single articles for the internal study or research purposes of the subscriber. The Photocopy License is not available to individuals or to certain other subscribers. The Photocopy License does not permit copying for any other purpose, such as copying for distribution to any third party (whether by sale, loan, gift or otherwise); as agent (express or implied) of any third party; for purposes of advertising or promotion; or to create collective or derivative works. All requests for permission to copy beyond the scope of the Photocopy License must be made to the Publisher. No copyright licensing organization in any territory has authority to grant such permission on the Publisher's behalf. Any unauthorized reproduction, transmission or storage may result in civil or criminal liability.

Rights and Permissions/Reprints of Individual Articles Permission to reproduce and/or translate material contained in this journal must be obtained in writing from the Publisher. Copies of individual articles may be obtained from SCAN, the Publisher's own document delivery service. For either service, please write or fax to: International Publishers Distributor at one of the addresses listed above.

Voluntary Page Charges The United States National Science Foundation has extended the allowance of page charge funds for payments to journals regardless of the publisher's commercial status. Previously this was reserved for only nonprofit society-sponsored journals. Voluntary page charge payments are now accepted for this journal, and authors may elect to pay any amount up to a maximum of \$25.00 per page. Payments will be refunded in the form of a voucher at 100% value of total payment. This voucher can be used by the author or the author's university library for any product or service offered by the Publisher, and thereby can be used to supplement library funding.

Negative Page Charges The principal author of each article will receive a voucher for his contribution in the amount of ECU 15.00 (US \$20.00, Yen 3,000), which can also be used to purchase the Publisher's products directly or through university libraries, thereby reducing costs of publications to those authors supporting the journal.
